

In the claims:

Please cancel Claim 2.

Please amend the Claims as follows:

1. (Currently amended) A polishing composition comprising:

- a) an abrasive;
- b) a fluoride salt; and
- c) an acetylenic alcohol;

wherein the acetylenic alcohol has at least two hydroxyl substituents.

2. (Cancelled)

3. (Currently amended) The polishing composition of Claim 2 1 wherein the acetylenic alcohol is 2,4,7,9-tetramethyl-5-decyn-4,7-diol.

4. (Previously presented) The polishing composition of Claim 1 wherein the acetylenic alcohol is a C₄-C₂₂ alkyne.

5. (Previously presented) The polishing composition of Claim 4 wherein the acetylenic alcohol is a C₁₂-C₁₆ alkyne.

6. (Previously presented) The polishing composition of Claim 1 wherein the abrasive is a colloidal abrasive.

7. (Previously presented) The polishing composition of Claim 6 wherein the colloidal abrasive is colloidal silica.

8. (Previously presented) The polishing composition of Claim 1 wherein the fluoride salt is ammonium fluoride.

9. (Currently amended) A method for chemical mechanical planarization of a substrate comprised of dielectric material, the method comprising the steps of:

- i. providing a substrate comprised of dielectric material in contact with a polishing pad;
- ii. providing a composition for chemical mechanical planarization comprising a) an abrasive; b) a fluoride salt; and c) an acetylenic alcohol; and
- iii. polishing the substrate with the composition to effect at least partial planarization of the substrate;

wherein the acetylenic alcohol of the composition has at least two hydroxyl substituents.

10. (Cancelled)

11. (Currently amended) The method of Claim ~~10~~ 9 wherein the acetylenic alcohol of the composition is 2,4,7,9-tetramethyl-5-decyn-4,7-diol.

12. (Previously presented) The method of Claim 9 wherein the acetylenic alcohol of the composition is a C₄-C₂₂ alkyne.

13. (Previously presented) The method of Claim 12 wherein the acetylenic alcohol of the composition is a C₁₂-C₁₆ alkyne.

14. (Previously presented) The method of Claim 9 wherein the abrasive of the composition is a colloidal abrasive.

15. (Previously presented) The method of Claim 14 wherein the colloidal abrasive is colloidal silica.

16. (Previously presented) The method of Claim 9 wherein the fluoride salt of the composition is ammonium fluoride.

Please add new Claims 17 and 18 as shown below:

17. (New) A polishing composition comprising:

- a) an abrasive;

b) a fluoride salt selected from the group consisting of ammonium fluoride, sodium fluoride, and potassium fluoride; and

c) an acetylenic alcohol;

wherein the acetylenic alcohol has at least two hydroxyl substituents.

18. (New) A polishing composition comprising:

a) an abrasive;

b) ammonium fluoride; and

c) 2,4,7,9-tetramethyl-5-decyn-4,7-diol.